

Title (en)  
APPARATUS FOR ELECTRON BEAM EVAPORATION

Title (de)  
VORRICHTUNG ZUM ELEKTRONENSTRAHLVERDAMPFEN

Title (fr)  
DISPOSITIF D'ÉVAPORATION SOUS FAISCEAU ÉLECTRONIQUE

Publication  
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Application  
**EP 07764905 A 20070628**

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Abstract (en)  
[origin: WO2008003425A1] The invention relates to an apparatus for electron beam evaporation, comprising a vacuum work chamber (2), a axial emitter (6) for generating an electron beam (7) by which a material (5) to be evaporated can be heated, and a diaphragm (9) disposed between the material (5) and a substrate (3) to be coated, the diaphragm being provided with at least one steam aperture (10) through which material vapor can flow to the substrate (3), wherein the diaphragm (9) comprises a magnetic system (14), by which the electron beam (7) can be deflected through the steam aperture (10) onto the material (5) to be evaporated.

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